NEWS RELEASE

SCREEN
DAINIPPON SCREEN MFG. CO.,LTD.

*Doc. No.: NR050621E*

June 21, 2005

# Dainippon Screen announces the release of its next generation 300 mm automated wet station, the FC-3100 — Providing enhanced technology and significantly reduced manufacturing and installation times.

Kyoto, Japan, June 21, 2005 — Dainippon Screen Mfg. Co., Ltd. (Headquarters: Kyoto, Japan / President: Akira Ishida) announced today it will commence sales on July 1, 2005 of its new 300 mm automated wet station, the FC-3100.

Continuing reductions in device geometries and cost factors associated with 300 mm production fabs impose increasing challenges on wafer processing equipment. Wet stations are no exception. With 90 nm technology in volume production, 65 nm devices being introduced, and 45 nm development well under way, it is imperative Dainippon Screen continue to provide improved cleaning solutions.

The new FC-3100 is Screen's next generation automated wet station built on the foundation of their market leading tool, the FC-3000. The FC-3000 has become a global standard in wet stations since its introduction in 1999. It has a remarkable 45.5% share[*1] of the overall auto wet station market and approximately a 70% share[*2] of the 300 mm market. Dainippon Screen anticipates these numbers will grow even further with the introduction of the FC-3100.

Enhancements made to the FC-3100 provide even greater process performance, stability, reliability, and cost of ownership. The FC-3100 employs a new modular design, improving configuration flexibility while suppressing manufacturing lead times and set-up time in customer's facilities. Improved robotics, new buffer design, and robust wafer scheduling algorithms provide 460 wafers per hour mechanical throughput capability.

New process technologies offered on the FC-3100 include the SCC or Single Chamber Clean module[*3]. The SCC combines the attributes and capabilities of the Once through Bath (for dilute chemical cleaning) and Low Pressure Dryer (LPD) in a single unit with controlled ambient processing. Both the FC-3000 and FC-3100 feature other new technologies that are indispensable in 65 nm processing, including; a low temperature drying option for dual gate applications, a Phosphoric Acid Concentration Feedback System that precisely measures and controls acid / water concentrations. These features and others make the FC-3100 the tool of choice for device manufacturers now and in the future.

✻ Detailed information on the FC-3100 will be on display at SEMICON WEST in San Francisco, CA, USA between July 12 and 14.

*1: According to research by Gartner Dataquest (April 2005), 2004 Worldwide Auto Wet Station market share. GJ05210

*2: According to SCREEN as of June 2005

*3: Optional

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## Date sales are expected to commence

July 1, 2005

## Suggested retail price in Japan (without tax)

Between 250 million and 400 million yen

✻ Exact price depends on specifications.

## Expected annual sales (first year)

20 units

**FC-3100**

Please download the photo from
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